

**INFORMATION DISCLOSURE STATEMENT**

Applicant : Masuda, et al.  
App. No : 10/568,126  
Filed : February 14, 2006  
For : POSITIVE PHOTORESIST  
COMPOSITION AND RESIST  
PATTERN  
Examiner : Chu, John S. Y.  
Art Unit : 1752

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 6 references to be considered by the Examiner. Also enclosed are 2 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement.

This Information Disclosure Statement is being filed before the mailing date of a final action and before the mailing of a Notice of Allowance. This Statement is accompanied by the fees set forth in 37 C.F.R. § 1.17(p). The Commissioner is hereby authorized to charge any additional fees which may be required or to credit any overpayment to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 9/26/07

By: Neil S. Bartfeld

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